METHOD AND APPARATUS FOR INSPECTING DEFECTS IN A SEMICONDUCTOR WAFER

ABSTRACT OF THE DISCLOSURE

In a wafer inspection and sampling system, wafer defects are detected and stored in a data store as defect data. Information is also provided, representative of clusters of defects on the wafer. A statistically based sampling of the defects is made to obtain a set of sampled defects. Subsequent detailed inspection and analysis of the sampled defects produces additional data which facilitate an understanding of process errors.

PA 3188705 v1